

Ultra-High-Temperature Precision Furnace for Single Crystal Growth

model CGF-20245U

[Outline]

This device is a high-vacuum high-frequency furnace that can maintain stable ultra-high temperatures (2000°C) for long periods.

Because special radiation-shielded tubing is used, heat loss from the crucible surface is minimized. Precisely controlled high temperatures can be maintained with high-frequency heating.

[Machine overview]



[Basic specifications]

Heating Temperature	2000°C
Furnace Design	dual pipe silica glass/ outside is water cooled.
Using Pressure Range	up to 10^{-7} torr (relative to absolute pressure)
Material of Crucible Shaft	tungsten
Travel stroke of crucible	200 mm
Normal Travel Speed	0.1–10 mm/hr (stability $\pm 0.5\%$ FS)
Fast-forward Speed	100 mm/min (fixed)
Special Radiation Shield Tube	equipped
Evacuation rate for Vacuum	TMP 160 L/s + RP 90 L/min
Configuration of	high-frequency transmitter/mating box/heating coil
High-frequency power source (heat source)	
High-frequency power specifications	nominal output 100 kW
Feedback adjustment	feedback control of high-frequency transmitter by measured actual temperature
Temperature control system	two color radiation thermometer and program controller



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